

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	34	resin and (heat\$3 with harden\$3) and dry\$3 and fluorine gas	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:01
S2	19	S1 and circuit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:02
S3	19	S1 and circuit\$2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:02
S4	4	S1 and circuit\$2 and lithography	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:04
S5	222	resin and (heat\$3 with harden\$3) and dry\$3 and fluorine with gas	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:06
S6	125	S5 and circuit	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:07
S7	17	S6 and lithography	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:07

S8	1	(US-5853953-\$).did.	USPAT	ADJ	ON	2010/07/29 15:10
S9	1	S8 and (water or "H. sub.2.0")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:10
S10	1	S8 and dry\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:15
S11	1	S8 and (expos\$3 or develop\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:19
S12	1	S8 and (UV or ultraviolet)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:35
S13	0	S8 and oxygen	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:40
S14	1	S8 and plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:40
S15	12230	oxygen plasma and photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:41
S16	4403	oxygen plasma with photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:41

S17	163	oxygen plasma treatment with photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:41
S18	32	oxygen plasma treatment with photoresist and resin	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:41
S19	1152	oxygen plasma with photoresist and fluorine	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:45
S20	470	oxygen plasma with photoresist and fluorine with gas	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:46
S21	0	S8 and hydrofluoric	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:50
S22	0	S8 and hydrofluoric	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:50
S23	1090	(fluorine with gas) and hydrofluoric acid and photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:51
S24	52	(fluorine with gas) and (hydrofluoric acid with concentration) and photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 15:51

S25	1	S8 and metal\$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:03
S26	1	S8 and circuit\$2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:04
S27	5403	(organic with conductive) and photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:08
S28	4069	(organic with conductive) and photoresist and circuit\$2	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:08
S29	316	S28 and fluorine with gas	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:09
S30	207	S28 and fluorine with gas and oxygen with plasma	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:09
S31	22	S30 and hydrofluoric acid	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:09
S32	1	(US-6169324-\$).did.	USPAT	ADJ	ON	2010/07/29 16:12
S33	1	S32 and conductive with organic	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:15

S34	0	S8 and olefin	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:18
S35	347378	olefin	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:18
S36	1	S8 and (acrylic or silicone or fluorine or polyimide or polyolefin or olefin or epoxy)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:21
S37	2	("5258257").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/07/29 16:25
S38	1	S37 and condensation	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:26
S39	0	S37 and condensation and acrylate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:26
S40	0	S37 and condensation and acrylic	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:26
S41	0	S8 and acryl	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:30

S42	0	alicyclic olefin resin same photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:35
S43	2	alicyclic olefin same photoresist	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:36
S44	0	S8 and carboxylate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:39
S45	1	S8 and anhydride	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:40
S46	1	S8 and alicyclic	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:48
S47	1	S8 and (alkali\$2 or bas\$2)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2010/07/29 16:54
S48	2	("7345000").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/07/30 13:29

EAST Search History (Interference)

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